

20th Brazilian Workshop On Semiconductor Physics

jeudi 15 septembre 2022

Oral: Rodrigo S. Pessoa (09:30 - 09:50)

time	[id] title	presenter
09:30	[21] Growth of Al ₂ O ₃ thin films using plasma-activated deionized water as a new oxidant in thermal atomic layer deposition process	Prof. S. PESSOA , R.